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OTHER INFORMATION
(Including Author, Title, Date, Pertinent Pages, Etc.)

*Examiner Initial	Cite No.	
<u>JO</u>	O1	Cobb, N., et al., "Experimental Results on Optical Proximity Correction with Variable Threshold Resist Model," <i>Optical Microlithography X, The International Society for Optical Engineering</i> 3051:458-468, March 1997.
<u>JO</u>	O2	Cobb, N.B., "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing," Ph.D. dissertation, University of California at Berkeley, Spring 1988, pp. 64-71.
<u>JO</u>	O3	Cobb, N., et al., "Mathematical and CAD Framework for Proximity Correction," <i>Optical Microlithography IX, The International Society for Optical Engineering</i> 2726: 208-222, March 1996.
<u>ZJO</u>	O4	Benchmark Technologies, OPC Reference Standard (J111A) Reticle, October 12, 1999.
<u>JO</u>	O5	"Resolution Enhancement Technologies (OPC/PSM)," July 16, 2002, Mentor Graphics Internet Site, Technical Papers.
<u>JO</u>	O6	Randall, J., et al., "Lithography Simulation With Aerial Image - Variable Threshold Resist Model," <i>International Conference on Micro and Nano Engineering</i> 46:59-60, September 1998.
<u>JO</u>	O7	Rieger, M.L. and J.P. Stirniman, "Using Behavior Modeling for Proximity Correction," <i>SPIE Proceedings, The International Society for Optical Engineering, Optical/Laser Microlithography VII</i> 2197:371-376, May 1994.
<u>JO</u>	O8	Schellenberg, F.M., et al., "SEMATECH J111 Project: OPC Validation," <i>SPIE Proceedings, Optical Microlithography XI</i> 3334:892-911, 1998.
<u>JO</u>	O9	Schellenberg, F.M., "Design for Manufacturing in the Semiconductor Industry: The Litho/Design Workshops," <i>Proceedings of the 12th Int'l. Conference on VLSI Design</i> , Jan. 10-13, 1999, pp. 111-119.
<u>JO</u>	O10	Schellenberg, F.M., "Sub-Wavelength Lithography Using OPC," <i>Semiconductor Fabtech</i> , 9th ed., March 1999.
<u>JO</u>	O11	Spence, C., et al., "Integration of Optical Proximity Correction Strategies in Strong Phase Shifters Design for Poly-Gate Layers," <i>SPIE Proceedings, 19th Annual Symposium of Photomask Technology</i> 3873:277-287, 1999.

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~~012 SPIE Proceedings, 19th Annual Symposium on Photomask Technology
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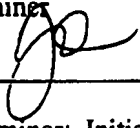
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Examiner



Date Considered

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*Examiner: Initial if reference considered, whether or not citation is in conformance with
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